In the Claims:

- The invention relates to a A layer system that filters sun 1. (Currently amended) and heat and can be applied to glass by means of a vacuum coating process, said system comprising at least one series of metal layers in addition to a respective series of lower dielectric layers that are positioned directly below said assembly and a respective series of upper dielectric layers that are positioned directly above said assembly, characterised in that at least one metal layer system (4) as well as one sandwiched between an upper (2) and one a lower (3) dielectric layer system are configured as a sandwich system in which, within the metal layer system (4), a metal layer (8) consisting of comprising at least one individual layer is encapsulated by an upper (9) and a lower (7) intermediate layer consisting of the comprising a hypostochiometrically nitrated or oxidised metal of the metal layer (8) and in which the lower (3) as well as the upper (2) dielectric layer system has a stochiometric layer (5, 11) of a metal or semiconductor oxide or metal or semiconductor nitride as well as at least one further hypostochiometric layer (6, 10) of the a same metal or semiconductor oxide or metal or semiconductor nitride whereby wherein within the dielectric layer systems (2, 3), the coatings layers are positioned in such a way that in comparison to the a neighbouring layer, the layer with the greater oxygen or nitrogen deficit of the metal or semiconductor oxide or metal or semiconductor nitride always lies on the a side turned towards the metal layer (8).
- 2. (Currently amended) Thermally treatable The layer system that filters sun and heat according to Claim 1, eharacterised in that the wherein an oxygen or nitrogen portion within a-the sandwich system is designed as a gradient.
- 3. (Currently amended) Thermally treatable The layer system that filters sun and heat according to Claim 1 or 2, characterised in that the wherein a dielectric of the dielectric layer systems (2, 3) is comprises a nitride, oxide or oxynitride of silicon.
- 4. (Currently amended) Thermally treatable The layer system that filters sun and heat according to Claim 1 or 2 characterised in that the wherein a dielectric of the dielectric layer systems (2, 3) is comprises a nitride or oxide of a metal or semiconductor

whereby the wherein a refractive index of this said nitride or oxide is more highly refractive in comparison with that a refractive index of the silicon nitride.

- 5. (Currently amended) Thermally treatable The layer system that filters sun and heat according to Claim 4, characterised in that wherein the dielectric of the dielectric layer systems (2, 3) is comprises a nitride or oxide of a metal or semiconductor that has a refractive index in the range of approx. 2.0 to 2.7 measured at a wavelength of 550nm.
- 6. (Currently amended) Thermally treatable The layer system that filters sun and heat according to one of Claims Claim 1 to 5 characterised in that wherein the metal layer (8) is composed of comprises a Ni:Cr alloy.
- 7. (Currently amended) The layer system that filters sun and heat according to one of Claims Claim 1 to 5, characterised in that wherein the metal layer (8) is composed of comprises chrome.
- 8. (Currently amended) The layer system that filters sun and heat according to one of the Claims Claim 1 to 5, characterised in that wherein the metal layer (8) is composed of comprises at least three individual layers of a metal that has electric conductivity in the a magnitude of 10⁷ s/m.
- 9. (Currently amended) The layer system that filters sun and heat according to Claim 8 characterised in that the wherein a middle individual layer of the metal layer (8) has an electric conductivity of approximately 6 * 10⁷ S/m.
- 10. (Currently amended) The layer system that filters sun and heat according to one of Claims Claim 8 or 9, characterised in that wherein the layer system has at least one further metal layer system with one further adjacent dielectric layer system so that both assemblies which constitute a periodic continuation of the an assembly sequence of the lower and upper dielectric layer systems (2, 3) and the metal layer system (4).

- 11. (Currently amended) The layer system that filters sun and heat according to one of Claims Claim 6 or 7, characterised in that wherein the stochiometric layer of the upper (2) and the lower (3) dielectric layer systems encompasses comprises a stochiometric silicon nitride layer with a thickness of approximately 5.0 nm to 200.0 nm (50Å to 2000 Å) and the a thickness of the at least one further hypostochiometric silicon nitride layer[[s]] of every dielectric layer system (2, 3) amounts to approx. 5.0 nm to 50.0 nm (50Å to 500Å) in total, that and the metal layer (8) has a thickness of approx. 1.0 nm to 100.0 nm (10Å to 1000Å) and every intermediate eoating (7, 9) layer has a thickness of approx. 1.5 nm to 20.0nm (15Å to 200Å).
- 12. (Currently amended) Thermally treatable The layer system that filters sun and heat according to Claim 8 characterised in that the wherein layer thicknesses of the available intermediate layers (7, 9) respectively above and below the metal layer (8) and/or the available dielectric layer systems (2, 3) respectively above and below the metal layer are identical.
- 13. (Currently amended) Thermally treatable The layer system that filters sun and heat according to one of Claims Claim 1 to 12, characterised in that wherein at least one hypostochiometric layer of the dielectric layer systems (2, 3) has such an oxygen or nitrogen deficiency that the an extinction coefficient of this said hypostochiometric layer lies in the a range between 1* 10⁻² to 1*10⁻³.
- 14. (Currently amended) Thermally treatable The layer system that filters sun and heat according to Claim 13 characterised in that wherein at least one hypostochiometric layer of the dielectric layer systems (2, 3) exhibit has such a an oxygen or nitrogen deficiency that the extinction coefficient of this said hypostochiometric layer lies in the a range between 2* 10⁻³ to 3* 10⁻³.
- 15. (Currently amended) Method for the manufacture of a thermally treatable layer system that filters sun and heat according to Claim 1 in which the

individual layers are applied one after the an other to a glass substrate by means of a vacuum coating characterised in that wherein at least one of the oxide or nitride layers are is applied in a reactive vacuum coating process from a metallic or semiconductive coating source and in the presence of oxygen or nitrogen as a reactive gas.

- 16. (Currently amended) Method A method for the manufacture of a thermally treatable layer system that filters sun and heat according to Claim 1 in which the individual layers are applied one after the an other to a glass substrate by means of a vacuum coating characterised in that wherein at least one of the oxide or nitride layers are is applied in a nonreactive or partially reactive vacuum coating process from a coating source which is composed of the stochiometric or hypostochiometric oxide or nitride of the material of the sandwich system and thereby wherein no or only small amounts of oxygen or nitrogen are added to the a working gas during the coating process.
- 17. (Currently amended) Method The method for the manufacture of a thermally treatable layer system that filters sun and heat according to Claim 16, characterised in that wherein oxygen or nitrogen with a volume content of less than 10% of the a volume of the working gas is added to the working gas during the coating process.
- 18. (Currently amended) Method-A method for the manufacture of a thermally treatable layer system that filters sun and heat according to Claim 3 according to one of Claims 15 or 16, characterised in that the wherein extraction of at least one of the dielectric layer systems (2 or 3) is carried out from a coating source containing primarily silicon which has an aluminium content of approximately 5 to 15%.
- 19. (Currently amended) Method A method for the manufacture of a thermally treatable layer system that filters sun and heat according to Claim 3 according to one of Claims 15 or 16, characterised in that the wherein extraction of at least one of the dielectric layer systems (2 or 3) is carried out from a coating source containing primarily silicon which has doping that increases the electric conductivity of the silicon coating source.

- 20. (Currently amended) Method for the manufacture of a thermally treatable layer system that filters sun and heat according to Claim 19, characterised in that wherein the extraction of at least one of the dielectric layer systems (2 or 3) is carried out from a coating source containing primarily silicon that has boron doping.
- 21. (Currently amended) Method The method for the manufacture of a thermally treatable layer system that filters sun and heat according to Claim 19, characterised in that wherein the extraction of at least one of the dielectric layer systems (2 or 3) is carried out from a coating source containing primarily silicon which has carbon doping.